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(54) **Title**: DEVICE FOR PARTICLE FREE HANDLING OF SUBSTRATES

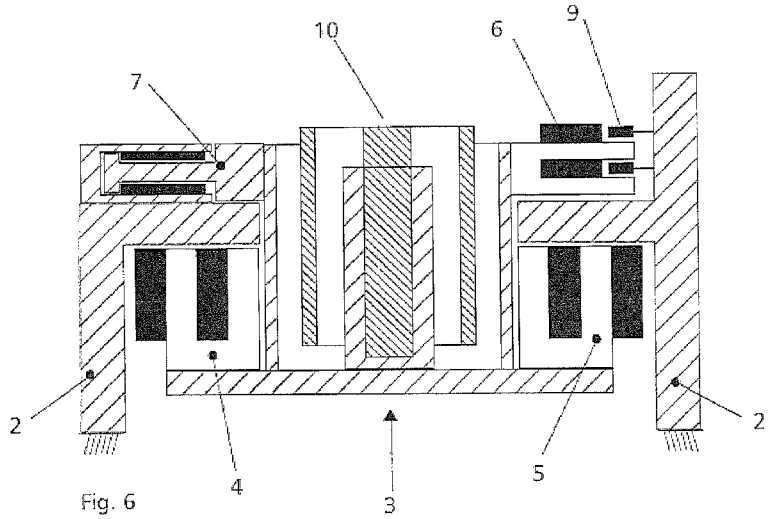



Fig. 6

(57) **Abstract**: The invention is concerned with a device for particle free handling of substrates according of micro technology within mini environments under clean room conditions. It is a task of the invention to provide a device for handling of substrates which works friction free and thus particle free. According the invention are designed several degrees of freedom for the device whereby at least the x-, y-, z-axis and a Φ-direction are supported magnetic and contact free and/or guided, whereby supporting and drive of each of the axis and direction is effected contact less electromagnetic and whereby the transmission of energy for bearing and driving is effected contact less. There is designed at least one active component (3) and at least one passive component (2), whereby the movable active component (3) is guided hanging at the fixed passive component (2) by a magnet bearing (5, 5) and whereby drive motor (7) which rides with the active component (3) is coupled with an energy supply over an electromagnetic coupling.

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